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Deposition rate of Ti film prepared by Explorer14 magnetron Sputterer

Swapil Paliwal
swapil@seas.upenn.edu

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Deposition rate of Ti film prepared by Explorer14 magnetron Sputterer (Graduate Student Fellow Program)

prepared by Swapil Paliwal (4/21/2014)
- Thickness measurement: P7 stylus profiler
- Deposition rate: 17.6 nm/min at 400 W DC